

METHOD AND STRUCTURE TO IMPROVE PROPERTIES OF TUNABLE ANTIREFLEC- TIVE COATINGS

Abstract

A method for improving the properties of tunable etch resistant anti-reflective coatings (TERA) is disclosed. The method includes annealing the deposited layer of TERA in an environment containing at least one of hydrogen and deuterium. The annealed layer has an increased concentration of hydrogen and/or deuterium as compared to the deposited film, and may also have an additional concentration of hydrogen or deuterium at the interface between the substrate and the layer of TERA.